

ABSTRACT OF THE DISCLOSURE

A method and apparatus for real-time detection of wafer defects. A method for real-time detection of wafer defects comprises the steps of providing a desired wafer before or
5 after a predetermined fabrication step and obtaining optical information thereof and comparing and analyzing the optical information of the desired wafer with corresponding reference information for instantaneously detecting possible wafer defects, wherein a predetermined action is performed
10 upon detection of wafer defects.